

In the Claims

This listing of claims will replace all prior versions, and listings, of claims in the specification:

Listing of Claims

1. (Currently Once Amended): A manufacturing method of a transfective TFT-LCD panel, comprising the steps of:

forming a first conductive layer on a substrate;

~~defining-patterning~~ the first conductive layer to form a gate;

forming a dielectric layer ~~therein on the substrate~~ to cover the gate;

forming a channel on the dielectric layer and the channel disposed over the ~~the~~ gate;

forming a photo-resist block;

forming a second conductive layer to cover the channel and the photo-resist block;

~~defining-patterning~~ the second conductive layer to form a source, ~~and a drain~~ and over the gate, meanwhile, forming a photo-reflective layer, wherein the source and the drain are disposed above the gate, and the photo-reflective layer is formed on the photo-resist block;

forming a protection layer ~~thereon~~ to cover the source, the drain and the photo-reflective layer;

~~defining-patterning~~ the protection layer, ~~forming to form~~ a first opening on the drain allowing part of the drain to be exposed, and ~~forming~~ a second opening on the photo-reflective layer allowing part of the photo-reflective layer to be exposed; and

forming a transparent electrode electrically connected to the drain and the photo-reflective layer via the first opening and the second opening.

2. (Original): A manufacturing method according to claim 1, wherein a capacitor electrode set under the photo-resist block is formed during the step of defining the first conductive layer.

3. (Original): A manufacturing method according to claim 1, wherein the first conductive layer is a first metal layer.

4. (Original): A manufacturing method according to claim 1, wherein the substrate is a glass substrate.

5. (Original): A manufacturing method according to claim 1, wherein the photo-resist block is composed of positive photo-resist.

6. (Original): A manufacturing method according to claim 1, wherein the second conductive layer is a second metal layer.

7. (Original): A manufacturing method according to claim 1, wherein the transparent electrode is composed of indium-tin oxide (ITO).

8. (Original): A manufacturing method of a transflective TFT-LCD panel equipped with a transmissive area and a reflective area, comprising the steps of:

forming a thin film transistor and a capacitor electrode on the substrate, wherein a photo-reflective layer within the reflective area and a source and a drain of the thin film transistor are formed simultaneously; and

forming a transparent electrode within the transmissive area.

9. (Currently Once Amended): A manufacturing method according to claim 8, wherein the photo-reflective layer is formed substantially~~largely~~ above the capacitor electrode.

10. (Original): A manufacturing method according to claim 8, wherein a photo-resist block is formed on the capacitor electrode prior to the formation of the photo-reflective layer.

11. (Canceled).

12. (Canceled).